

Achieving the Cutting-edge —

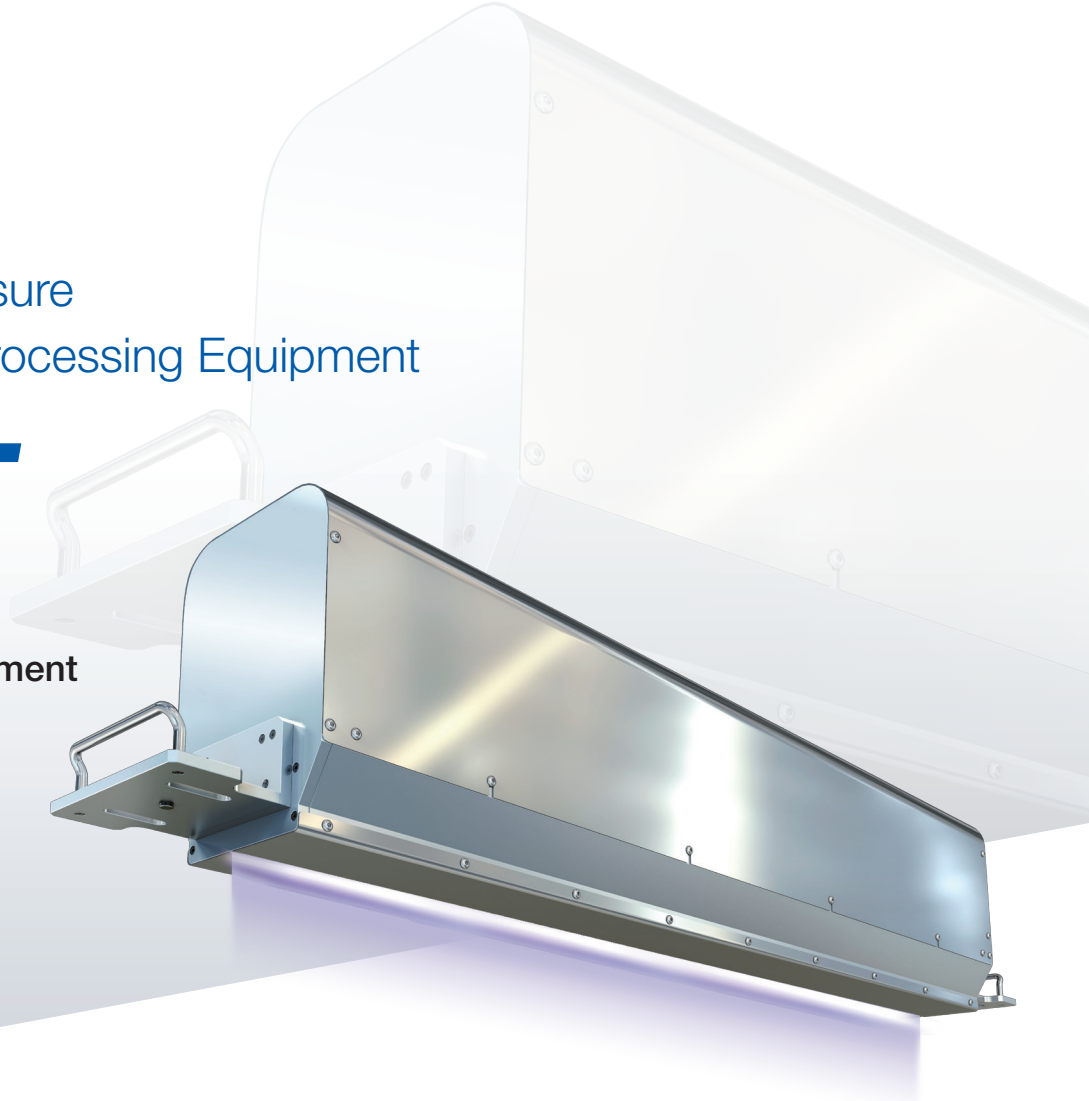
SEKISUI
Sekisui Chemical
Full of Surprises

Atmospheric-Pressure

Remote Plasma Processing Equipment



Low-temperature treatment
& electrical field
shielding structure
prevents damage



Features & Equipment specifications

1 »

No damage

Low-temperature treatment & electrical field shielding structure prevents heat and electrical damage

2 »

Advanced treatment performance

High-speed (10 m/min) treatment at 10° or under (treats glass substrates for LCD)

3 »

Extensive lineup

Handles widths from 160 to 3400 mm

4 »

Extensive and proven results

Adopted in LCD plants and numerous other production processes

Widths handled

160 to 3400 mm

Utility



Power, Treatment gas (N₂, CDA), Exhaust, Cooling water

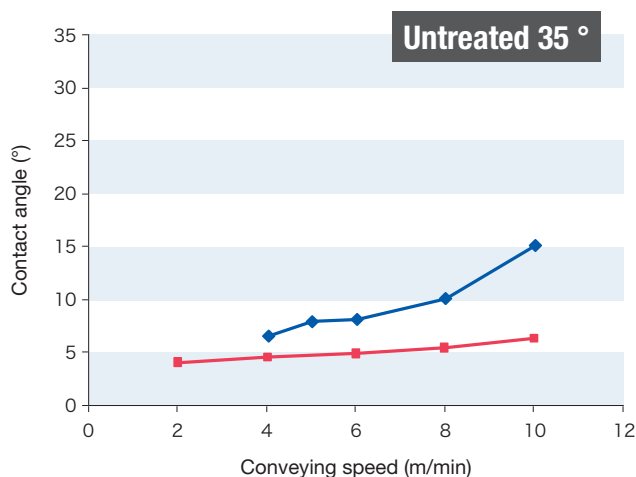
Applications

Field	Usage
LCD	Increases the wettability of glass surfaces, improves the wet cleaning effect
Touch panels, OLED, etc.	Reforms the surface of conductive film, pretreatment for bonding

Basic treatment performance

► Contact angle data of glass substrate (dependence on conveying speed)

[Tested substrate] Bare Glass
 Atmospheric-Pressure Plasma
 EUV



► Relation between conveying speed and changes in the substrate temperature

[Tested substrate] Bare Glass

